

All Active Equipment Sep 15, 2016, 5:15 AM

Name	Description	Location
4ptprb	Four Point Probe - Miller Design/Automat	380
4ptprb2	Four Point Probe - Manual	380
accounting	Use to request accounting adjustments	520
afm2	Digital Instruments AFM	cory-151
aln2	Tegal Endeavor AT sputter deposition sy	584
amatepi	epitaxial silicon / germanium deposition	586
amst	AMST Molecular Vapor Deposition	582A
aptchrome	APT chrome mask developer	382a
aptemul	APT emulsion mask developer	382a
asap-liftoff	Liftoff System - Model ASAP LOM6100	582A
asiq	Tencor AS500 Profilometer	584
asm1300	ASML 5500/300 DUV Stepper	384
autoprobe	Electroglass Autoprobe in DCL	cory-355
axcelis	Axcelis photoresist UV bake system	584
bagsealer	Plastic Bag Thermal Sealer	593
bottlewash	For Problem Reports - No Enable Required	582A
bottlewash2	For Problem Reports - No Enable Require	397
cambridge	Cambridge Fiji F200 Plasma ALD	586
canon	Canon 4X wafer stepper	382
cascade1	Cascade Probe Station - 1	cory-355
cascade2	Cascade Probe Station - 2	cory-355
cde-resmap	CDE 4-ptprb Automated Mapper, 2" -12"	380
centura-3-5	Centura Compound Etch - Chamber A	586
centura-met	Centura DPS Metal Etcher - Ch C	586
centura-mxp	Centura oxide etch chamber - Ch B	586
cha	CHA E-beam Evaporator	582
chp	Chemical Hygiene Plan	nanolab
cmp	Strausbaugh CMP	cory-190
compound-ox	Table Top Wet-Oxidation Furnace for III-	382
computers	catch all for computer related items	nanolab
cpd	Tousimis 915B 6" Critical Point Dryer	382
cpd2	Tousimis 815A 1.5" Critical Point Dryer	382
cpdsink	CPD Sink - Bay 382	382
crestec	Crestec EBEAM Lithography	384
dcl	For Problem Reports - No Enable Require	cory-373
dektak	Dektak Model 3030 Surface Profilometer	380
disco	Disco DAD3240 Automated Dicing Saw	582A
drystation1	Drying Station - Bay 382	382
ebeam1	Electron Beam 10 kW 4-pocket Evaporator	382
edwards	Edwards Sputter System	582
edwardseb3	Edwards 306 E-Beam System	582
edx	Energy-dispersive X-ray Spectroscopy	384
elevchem	For Problem Reports - No Enable Required	586
elevlab	Lab Passenger Elevator	580
ellips	Ellipsometer - Gaertner Stokes	386

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Name	Description	Location
facility	To Report NanoLab Building Problems	nanolab
fei-sem	FEI Nova NanoSEM650	131
finetech	Finetech Die Attachment Bonder	cory-153
flexus	Tencor FleXus FLX2320 Stress Gauge	380
flipchip	Suss FC150	382
ftir	General use FFT Infrared Spectrometer	380
gartek	Gartek sputterer	582
gcapg	GCA 3600 pattern generator	382a
gcaws2	GCA G-Line 10X Wafer Stepper	384
gcaws6	GCA 8500 5X I-line	384
glovebox2	Glovebox for Inert Atmosphere	380
gnpcmp	G&P Poli 500 CMP	582A
headway1	Headway Spinner In msink3	382
headway2	Headway Spinner - Standalone	382
hld	Alcatel Model 180 T Helium Leak Detector	nanolab
hotplates	Hotplates	382
ionmill6	Pi Scientific 6" Ion Beam Mill	584
ircam	Infrared Source & Video Camera	380
irscope	Infrared Microscope	380
keyence	Recharge digital microscope	380
kruss	Kruss Contact Angle Analyzer	582A
ksaligner	Karl Suss Mask/Bond Aligner	382
lacvd	Laser Assisted Chemical Vapor Deposition	597
lam6	Lam 4526 Oxide Etch	584
lam7	Lam Research 9626 Aluminum Etch	584
lam8	9426 Lam Research TCP MOS Poly Etch	584
lamovpe	Laser Assisted Metal-Organic Vapor Phase	597
linewidth	Linewidth & Feature Measuring System	380
linewidth2	Zeiss Feature Measuring Microscope	584
maskcopy	Ultratech mask copier	382a
matrix	Matrix 106 Resist Remover	384
matrix-etch	Matrix 303 plasma etcher	584
metricon	Prism-coupled refractive index analyzer	380
microscope1	Nikon Optiphot 200 located in Bay 384	384
microscope2	Nikon Optiphot 150 in bay 384	384
microscope3	Leitz Ergolux in bay 382	382
microscope4	Leitz Metalloplan in PG area, bay 382A	382a
microscope5	MM Stereo-scope in Bay 380	380
microscope6	Leitz Secolux in FEI room 131	131
microscope7	WILD M450 Stereo-scope	131
microscope8	Zeiss Axioplan2 Microscope in Bay 584	584
mrc944	MRC Sputtering System with Sputter-Etch	584
msink1	Tank Photoresist Strip and Develop	382
msink10	Red-room msink	382a
msink12	Compound semiconductor dep preparation	586

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Name	Description	Location
msink14	Epi Si/Ge deposition pre-clean	586
msink16	General purpose fume hood/wet process	582A
msink18	General purpose fume hood/wet process	582A
msink2	Heated Strip and Manual Develop Station	382
msink20	General purpose fume hood/wet process st	582A
msink3	SS, manual lithography, headway spinner	382
msink4	KOH & TMAH Silicon Etch	382
msink5	HF release etch wet process station	382
msink6	furnace pre-clean	384
msink7	Hot Phosphoric, HF, Silicon Etch (Bay 38	386
msink8	post PR cleaning	384
nanoduv	Nanospec/DUV Microspectrophotometer	380
nanospec	Nanospec AFT film thickness measuring sy	384
nanospec-cmp	NanoSpec AFT film thickness monitor	cory-190
nanotube	Nanotube Furnace	380
netscope	Leica IMN200 Microscope	382
nrc	NRC evaporator	582
olympus	Olympus LEXT 3D Laser Measuring Microsco	380
oven	NanoLab Ovens	382
oxford	Oxford Plasmalab System 100	584
oxford-icp	Oxford Instruments PlasmaPro100 ICP65	584
oxford2	Oxford Plasmalab 80 PECVD	584
oxfordpecvd4	Oxford Cluster Chamber4 PECVD	586
oxfordpvd1	Oxford Cluster Chamber1 Sputter Dep	586
oxfordpvd2	Oxford Cluster Chamber2 Sputter Dep	586
parylene	Specialty Coating Systems PDS2010	582A
picosun	Picosun Sunale R150 ALD	586
plotter	Hewlett Packard Wide Plotter	520
pqecr	Plasma Quest ECR PECVD	584
primaxx	Primaxx SPTS uEtch HF Vapor Etcher	382
primeoven	Yield Engineering Systems YES - 5	384
probe1	Large black Faraday cage with probe stat	380
ptherm	Plasmatherm reactive ion etcher	582
quintel	Quintel Q4000-6IR Contact Printer	382
raman-scope	Laser-based Raman Spectroscopic Microsco	380
randex	Randex sputtering system	582
refrigerators	Refrigerators for Chem Storage 381 & 393	nanolab
reichert	Reichert Polylite inspection microscope	380
resources	To Request Restock of Lab Consumables	nanolab
rtp1	AccuThermo AW610 RTP for III/V or PZT	582
rtp2	AccuThermo AW610 RTP III/V -no metal	582
rtp3	AccuThermo AW610 RTP Si Non-MOS	386
rtp4	AccuThermo AW610 RTP Si MOS Clean	386
rtp8	AccuThermo AW810 RTP Si MOS Clean	386
safety	Use to enter any lab related safety prob	nanolab

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Name	Description	Location
sca	Surface Charge Analyser	386
sem-coater	Denton II Desktop SEM AU/Pd Coater	380
semi	Semigroup plasma etcher	584
shippingstation	Table and accessories for shipment prep	593
sinkcmp	CMP Wet-sink	cory-190
sinkcmp2	Sink in 582A for dicso and gnpcmp	582A
sopra	Sopra Variable Angle/Frequency Ellips	380
sp3	sp3 CVD Diamond Coating System	595
sp3seeding	sp3 Diamond Wafer Seeding	582A
srmsink1	Spin Rinser Dryer at mskin1 - Veriteq	382
srmsink14	Semitool Spin Rinse Dryer at msink14	586
srmsink2	Spin Rinse Dryer at msink2 (382)	382
srmsink6	Semitool Spin Rinse Dryer 880-S	386
srmsink8	Veriteq Spin Rinser Dryer	386
sts-oxide	APS deep oxide etch	584
sts2	ICP pulsed gas deep silicon etch	584
svgcoat1	SVG 8600 6" Coat & Bake (front track)	384
svgcoat2	SVG 8600 4" Coat & Bake (rear track)	384
svgcoat3	SVG 8600 6" LOR & BARC Coat & Bake Track	384
svgcoat6	SVG8800 6" Coat Track	384
svgdev1	SVG8600 6" Develop Track	384
svgdev2	SVG8600 4" Develop Track	384
svgdev6	SVG8800 6" Develop Track	384
technics-c	Technics VLSI plasma etch	584
telephones	Lab, office phone sets and Room 158 PBX	520
tensiometer	Sigma 701 Tensionmeter	582A
tescal	Technical Eningeering Services Thermal E	582
topgun	3 target RF DC co-sputtering system	584
tystar1	Tystar 6" Wet/Dry Oxidation	386
tystar10	Tystar LPCVD Doped Poly	386
tystar11	Tystar LPCVD Doped LTO	386
tystar12	Tystar Doped LTO	386
tystar13	Tystar 6" POCL3	386
tystar14	Tystar 6" Solid-Source Boron	386
tystar15	Tystar 6" LPCVD Silicon Carbide	386
tystar16	Tystar 6" Doped Poly LPCVD	386
tystar17	Tystar LPCVD Low Stress Nitride	386
tystar18	Tystar 6" MOS Sinter	386
tystar19	Tystar LPCVD Si/Ge, MOS	386
tystar2	Tystar 6" Wet/Dry Oxidation	386
tystar20	Tystar Si/Ge LPCVD for MEMS	386
tystar3	Tystar 6" Wet/Dry Oxidation	386
tystar4	Tystar 6" Wet/Dry Oxidation	386
tystar5	Tystar 200mm Wet/Dry Oxidation	386
tystar6	Tystar 200mm N-Type Doping	386

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Name	Description	Location
tystar7	Tystar 200mm P-Type Doping	386
tystar9	Tystar LPCVD Nitride	386
ultek2	Ultek2 Angled Cooled Chuck E-Beam Evapor	582
uvbake	Fusion Photostabilization System	384
uvflood	Dymax 2000 - Timed UV Flood Exposures	382
uvscope	Leica I-line Microscope	384
vacoven	YES (Yield Eng. Systems) 450PBS-29	582A
vacoven2	Vacuum Oven adjacent to sem-coater	380
vwr2	VWR Bake Oven	382
westbond	West Bond 7400B Al wire bonder	380
westbond2	West Bond 7400B Au wire bonder	380
wyko	Wyko Optical Profilometer	380
xdif	X-Ray Diffractometer	380
xetch	XeF2 Bulk Silicon Etcher	582
yes-g500	YES-G500 Plasma Cleaning System	380
zeiss-sem	Zeiss Scanning Electron Microscope	384